

AMENDMENT

In response to the Office Action of November 6, 2001, please amend the above-identified application as follows:

In the Claims:

Please amend claim 1 as follows:

1.(AMENDED) A coaxial polishing-dressing apparatus comprising:
[a polishing platen having an upper surface on which a polishing pad is
affixed, said polishing platen being rotated in one direction along a
central axis thereof;]
5 a plurality of coaxial polishing-dressing head assemblies each having a
lower nesting surface opposed to an upper surface of the polishing pad
on said polishing platen, a nesting means releasably holding a substrate
to be polished, said coaxial assembly means rotating along a central axis
thereof and pressing the substrates on a radial portion of said rotating
10 polishing pad;
8027 annular dressing rings for dressing said polishing pad are positioned
coaxially encircling each nested substrate, said annular dressing
rings are removably attached to said lower surface of a plurality of
substrate nesting support heads, and
15 compressing means for applying a polishing and dressing pressure to said
coaxial polishing-dressing head assemblies, whereby the substrate
polishing-dressing head assemblies are pressed against the upper surface
of the polishing pad.